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XA-7889A Re

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

Kenji NISHI

Appln. No.: 08/994,758

Group Art Unit: 2851

Filed: December 19, 1997

Examiner: A. Mathews

For: PROJECTION EXPOSURE APPARATUS

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SUPPLEMENTAL AMENDMENT

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

Please amend the above-identified patent application as indicated below.

RECEIVED  
AUG 23 1999  
TC 2600 MAIL ROOM

IN THE CLAIMS:

Please add the following new claims:

- 1        --143. An exposure apparatus in which a portion of a  
2        pattern of an original is projected onto a substrate and in  
3        which the original and the substrate are scanned  
4        synchronously such that the pattern of the original is  
5        transferred to the substrate, said apparatus comprising:  
6        first and second stages, one of which is for scanningly  
7        moving the original and the other of which is for scanningly  
8        moving the substrate;

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